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(21) International Application Number: PCT/US98/19677 (22) International Filing Date: 22 September 1998 (22.09.98) (30) Priority Data: 08/936,010 23 September 1997 (23.09.97) US (71)(72) Applicant and Inventor: OLIN MICROELECTRONIC CHEMICALS, INC. [US/US]; 501 Merritt 7, Norwalk, CT 06856 (US). (72) Inventor: HONDA, Kenji; 8 Plymouth Drive, Barrington, RI 02806 (US). (74) Agent: GREELEY, Paul, D.; Ohlandt, Greeley, Ruggiero & Perle, L.L.P., 9th floor, One Landmark Square, Stamford, CT 06901-2682 (US).		(81) Designated States: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, GH, GM, HR, HU, ID, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, UZ, VN, YU, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG). Published <i>With international search report.</i>
(54) Title: AQUEOUS RINSING COMPOSITION (57) Abstract The present invention is directed to an aqueous post-strip rinsing composition, comprising (1) water; (2) at least one water-soluble organic acid; and (3) at least one water-soluble surface-active agent, the rinse solution having a pH in the range from about 2.0 to about 5.0. The present invention is also directed to a method of using the above composition to remove residues from a semiconductor substrate.		